

20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[TB3] CMP Cleaning Evolution
Session Date:	November 15 (Tue.), 2022
Session Time:	14:30-16:30
Session Room:	Room B (Grand Ballroom 1, 2F)
Session Chair:	Dr. Woojae Lee (ENF Tech., Korea)

[TB3-1] [Invited] 14:30-15:00

New Cleaning Solution Concepts for Advanced Technologies – from Chemical Supplier View
Andreas Klipps (BASF, Germany)

[TB3-2] [Invited] 15:00-15:30

Challenges in Selective Silicon Nitride Etching for 3D NAND Integration
Sangwoo Lim (Yonsei Univ., Korea)

[TB3-3] [Invited] 15:30-16:00

Development of a Membrane Process for Small Particle Removal in CMP Slurry and Post-CMP Cleaning
Sanghyeon Park, Jaewon Lee, Eungchul Kim, and Taesung Kim (Sungkyunkwan Univ., Korea)

[TB3-4] [Invited] 16:00-16:30

Post CMP Cleaning: Its Trend and Challenges
Jingoo Park (Hanyang Univ., Korea)